

Standard Carbide Etch Recipe

Vision RIE 2

January 1, 2013

Equipment

Equipment	Vision RIE 2
Manufacture	Advanced Vacuum
Model	Vision-320 RIE
Platen size	12 in
Platen Material	Graphite

Recipe

Recipe Name	Standard Oxide	
Gas	CHF ₃	45 sccm
	O ₂	5 sccm
Platen Power	250 W	
RF Frequency	13.56 Mhz	
Chamber Pressure	40 mTorr	

Results ^a

Material	PECVD SiC ^b
Etch Rate	N/A A/min ^c
Uniformity	N/A % ^d
Mask:	Microposit SC1827 ^e
Selectivity (vs. PR)	N/A

^a: All data is updated as the date indicated above

^b: Carbide film was prepared with the *Standard Carbide recipe* in Oxford PECVD left

^c: An average value from 8 min etch

^d: Etching depth variation across a 4" wafer, defined as std/average

^e: Photo-resist was pre-baked @115 °C for 40 sec on a hotplate